EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	278	(resist photoresist) same ash$3 same (CO2 "CO.sub."$2 (carbon near5 dioxide)) same (oxygen "O.sub.2" "O.sub."$2)	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 16:41
L2	249	1 and semiconductor	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 15:54
L3	246	2 and (etch$3 pattern$3)	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 15:54
L4	236	3 and substrate	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 15:28
L5	248	2 and (etch$3 pattern$3 remov$3)	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 15:27
L6	238	5 and substrate	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 16:34
L7	123	(resist photoresist) same ash$3 same (SO2 "SO.sub."$2 (sulfur near5 dioxide)) same (oxygen "O.sub.2" "O.sub."$2)	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 16:42
L8	118	7 and semiconductor	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 15:54
L9	115	8 and (etch$3 pattern$3)	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 16:35
L10	37	(resist photoresist) same ash$3 same (NO2 "NO.sub."$2 (nitrogen near5 dioxide)) same (oxygen "O.sub.2" "O.sub."$2)	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 16:43
L11	33	10 and substrate	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 16:34
L12	33	11 and (etch$3 pattern$3)	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 16:35

L13	12	(resist photoresist) same ash$3 same (CO2 "CO. sub."$2 (carbon near5 dioxide)) same (oxygen "O.sub.2" "O.sub."$2)	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2007/06/23 16:41
L14	1	(resist photoresist) same ash$3 same (SO2 "SO.sub. "$2 (sulfur near5 dioxide)) same (oxygen "O.sub.2" "O.sub."$2)	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2007/06/23 16:42
L15	1	(resist photoresist) same ash$3 same (NO2 "NO.sub. "$2 (nitrogen near5 dioxide)) same (oxygen "O.sub.2" "O.sub."$2)	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2007/06/23 16:43
L16	2	(resist photoresist) same (remov$3 trim$4) same (NO2 "NO.sub."$2 (nitrogen near5 dioxide)) same (oxygen "O.sub.2" "O.sub."$2)	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2007/06/23 16:44

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	74	(etch43 pattern$3 trim$4) near50 (resist photoresist) near50 ((carbaon near5 dioxide) CO2 "CO.sub."$2 (sulfur near5 dioxide) SiO2 "Si.sub."$2 (nitrogen near5 dioxide) NO2 "NO.sub."$2) near50 (oxygen "O.sub.2" O2 "O.sub."$2)	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 12:07
L2	87	(etch43 pattern$3 trim$4) near50 (resist photoresist) near50 ((carbon near5 dioxide) CO2 "CO.sub."$2 (sulfur near5 dioxide) SiO2 "Si.sub."$2 (nitrogen near5 dioxide) NO2 "NO.sub."$2) near50 (oxygen "O.sub.2" O2 "O.sub."$2)	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 12:17
L3	865	(etch43 pattern$3 trim$4) same (resist photoresist) same ((carbon near5 dioxide) CO2 "CO.sub."$2 (sulfur near5 dioxide) SiO2 "Si.sub."$2 (nitrogen near5 dioxide) NO2 "NO.sub."$2) same (oxygen "O.sub.2" O2 "O.sub."$2)	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 14:32
L4	778	3 not 2	US-PGPUB; USPAT; USOCR	OR	ON	2007/06/23 12:18
L5	95	(etch43 pattern$3 trim$4) same (resist photoresist) same ((carbon near5 dioxide) CO2 "CO.sub."$2 (sulfur near5 dioxide) SiO2 "Si.sub."$2 (nitrogen near5 dioxide) NO2 "NO.sub."$2) same (oxygen "O.sub.2" O2 "O.sub."$2)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/23 14:35